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Substitute for form 1449/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Sheet

1

of

5

Complete if Known

Application Number	10/800,110
Filing Date	March 12, 2004
First Named Inventor	A. Smith
Art Unit	Not yet assigned 1756
Examiner Name	Not yet assigned Young
Attorney Docket Number	38203-6295

U. S. PATENT DOCUMENTS

Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
/CY/	A	US- 5,285,236	02/08/1994	Jain	
	B	US- 5,757,507	05/26/1998	Ausschnitt et al.	
	C	US- 5,828,455	10/27/1998	Smith et al.	
	D	US- 5,877,861	03/02/1999	Ausschnitt et al.	
	E	US- 5,978,085	11/02/1999	Smith et al.	
✓	F	US- 6,079,256	06/27/2000	Bareket	
	G	US- 6,356,345	03/12/2002	McArthur et al.	
/CY/	H	US- 6,573,986	06/03/2003		
		US-			

FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages Or Relevant Figures Appear	T ⁶
		Country Code ³ "Number ⁴ "Kind Code ⁵ (if known)				

Examiner Signature

/Christopher Young/ (03/22/2007)

Date Considered

03/22/2007

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Substitute for form 1449/PTO				Complete if Known	
				Application Number	10/800,110
				Filing Date	March 12, 2004
				First Named Inventor	A. Smith
				Art Unit	Not yet assigned
				Examiner Name	Not yet assigned
Sheet	2	of	5	Attorney Docket Number	38203-6295

NON PATENT LITERATURE DOCUMENTS					
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.			
/CY/	I	G. Muller, "The Waferstepper Challenge: Innovation and Reliability Despite Complexity", Version 1, pp. 1-11, September 10, 2003.			
	J	"KLA 5105 Overlay Brochure", KLA-Tencor			
	K	H.G. Müller et al., "Large Area Fine Line Patterning by Scanning Projection Lithography", MCM Proceedings, pp. 100-104, 1994.			
	L	J. van Schoot et al., "0.7 NA DUV Step & Scan System for 150nm Imaging with Improved Overlay", SPIE Vol. 3679, pp. 448-456, 1999.			
	M	M.A. van den Brink et al., "Direct-Referencing Automatic Two-Points Reticle-To-Wafer Alignment Using a Projection Column Servo System", SPIE, Optical Microlithography V, Vol.			
	N	A. Erdmann et al., "Influence of Optical Nonlinearities of Photoresists on the Photolithographic Process: Applications", SPIE, Vol. 2726-29, 1996.			
	O	J.H. Bruning, "Optical Lithography - Thirty Years and Three Orders of Magnitude", SPIE, Vol. 3051, pp. 14-27.			
	P	B.E. Newnam et al., "Development of XUV Projection Lithography at 60-80 nm", SPIE, Vol. 1671, pp. 419-436, 1992.			
↓	Q	J.E. Bjorkholm et al., "Reduction Imaging at 14 nm Using Multilayer-coated Optics: Printing of Features Smaller than 0.1 •m", J. Vac. Sci. Technol. B 8 (6), pp. 1509-1513, 19			
/CY/	R	"Quaestor Q7 Brochure", Bio-Rad Semiconductor Systems.			

Examiner Signature	/Christopher Young/ (03/22/2007)	Date Considered	03/22/2007
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(Use as many sheets as necessary)</i>				Application Number	10/800,110
Sheet	3	of	5	Filing Date	March 12, 2004
				First Named Inventor	A. Smith
				Art Unit	Not yet assigned
				Examiner Name	Not yet assigned
				Attorney Docket Number	38203-6295

NON PATENT LITERATURE DOCUMENTS						
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.				T ²
/CY/	S	D. MacMillen et al., "Analysis of Image Field Placement Deviations of a 5X Microlithographic Recuction Lens", SPIE Vol. 334, pp. 78-89, 1982.				
	T	G.C. Robins et al., "Experimental Assessment of Pattern and Probe-Based Aberration Monitors", SPIE, Microlithography Proceedings, Vol. 5040-149, pp. 1-12, 2003.				
	U	J. Sung, "Aberration Measurement of Photolithographic Lenses by Use of Hybrid Diffractive Photomasks", Applied Optics, Vol. 42, No. 11, pp. 1987-1995, April 10, 2003.				
	V	International Technology Roadmap for Semiconductors, 2001 Edition", SEMATECH, pp. 1-21.				
	W	F. Schellenberg, "Resolution Enhancement with OPC/PSM", Future Fab International, Vol. 9, 2000.				
	X	I. Pollentier et al., "Thinking Outside the Box for Improved Overlay Metrology", SPIE Microlithography Proceedings, Vol. 5038, pp. 12-16, 2003.				
	Y	R. Martin et al., "Measuring Fab Overlay Programs", SPIE Metr. Inspection, and Process Control for Microlithography, XIII, pp. 64-71, March 1999.				
	Z	R. DeJule, "Mix-and-Match: A Necessary Choice", Semiconductor International, pp. 66-76, February 2000.				
↓	AA	J. Armitage, "Analysis of Overlay Distortion Patterns", J. Kirk, SPIE, Vol. 921, pp. 207-221, 1988.				
/CY/	AB	J. Wyant et al., "Basic Wavefront Aberration Theory for Optical Metrology", ISBN 0-12-408611-X, Chapter 1, pp. 1-53, 1992.				

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				First Named Inventor	A. Smith
				Art Unit	Not yet assigned
				Examiner Name	
Sheet	4	of	5	Attorney Docket Number	38203-6295

NON PATENT LITERATURE DOCUMENTS					
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.			
/CY/	AC	T. Brunner, "Impact of Lens Aberrations on Optical Lithography", IBM, Vol. 41, pp. 1-2, 1997.			
	AD	"TWINSCAN 1100 Product Literature" ASML.			
	AE	C. Ausschnitt, "Distinguishing Dose from Defocus for In-line Lithography Control", SPIE, Vol. 3677, pp. 140-147, 1999.			
	AF	L. Thompson et al., "Introduction to Microlithography", ACS, 2nd Edition, 1994, p. 69.			
	AG	G. Moore, "Cramming More Components Onto Integrated Circuits", Electronics, Vol. 38, No. 8, 1965.			
	AH	P. Rai-Choudhury, "Handbook of Microlithography, Micromachining, and Microfabrication", SPIE Press, Microlithography, Vol. 1, pp. 417, 1997.			
	AI	M.T. Takac et al., "Self-Calibration in Two-Dimensions: The Experiment", SPIE Vol. 2725, pp. 130-146.			
	AJ	M.A. van den Brink et al., "Matching Management of Multiple Wafer Steppers Using a Stable Standard and a Matching Simulator", SPIE Integrated Circuit Metrology, Inspection, an			
↓	AK	M.R. Raugh, "Error Estimation for Lattice Methods of Stage Self-Calibration", SPIE Vol. 3050, pp. 614-625.			
/CY/	AL	T.F. Hasan et al., "Automated Electrical Measurements of Registration Errors in Step-and-Repeat Optical Lithography Systems", IEEE Transactions on Electron Devices, Vol. ED-27			

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/CY/	AM	C.A. Mack, "Inside PROLITH: A Comprehensive Guide to Optical Lithography Simulation", pp. 137-151.			
/CY/	AN	M. Dusa et al., "Comprehensive Focus-Overlay-CD Correlation to Identify Photolithographic Performance", SPIE Vol. 2726, pp. 545-554.			
/CY/	AO	A.J. de Ruyter et al., "Examples of Illumination Source Effects on Imaging Performance", Arch Chemicals Microlithography Symposium, pp. 1-8, September 22, 2003.			

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